AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions of claims in the application.

Listing of Claims

Claim 1 (currently amended): A plating bath for formation of a thin resistance layer on a

surface of a conductive base, comprising: wherein said plating bath includes

nickel ions; [[and]]

sulfamic acid or its salt; as essential components and

at least one of phosphoric acid, phosphorous acid, hypophosphorous acid, and salts of the

same at a concentration of phosphorus of 20 to 150g/L.

Claim 2 (currently amended): A plating bath for formation of a thin resistance layer as set

forth in claim 1, further comprising wherein said plating bath further includes at least one of

sulfuric acid, hydrochloric acid, and salts of the same.

Claim 3 (currently amended): A plating bath for formation of a thin resistance layer as set

forth in claim 1, wherein a pH of the plating bath is made not more than 6.

Claim 4 (currently amended): A plating bath for formation of a thin resistance layer as set

forth in claim 2, wherein a pH of the plating bath is made not more than 6.

Claim 5 (original): A method of formation of a thin resistance layer in a plating bath as set

forth in any one of claims 1 to 4, wherein said thin resistance layer is formed in a range of bath

temperature of 30 to 80°C.

Claim 6 (original): A method of formation of a thin resistance layer in a plating bath as set

forth in any one of claims 1 to 4, wherein said thin resistance layer is formed in a range of current

density of 1 to 30 A/dm<sup>2</sup>.

Claim 7 (original): A method of formation of a thin resistance layer in a plating bath as set

forth in any one of claims 1 to 4, wherein said thin resistance layer is formed using an insoluble

anode.

Claim 8 (currently amended): A conductive base with a resistance layer wherein a thin

resistance layer comprised of an Ni alloy layer containing 2 to 30 wt% of P is formed on the

surface of the conductive base by a method of formation of a thin resistance layer in a plating

bath as set forth in any one of claims 1 to 4 in a range of bath temperature of 30 to 80°C.

Claim 9 (currently amended): A conductive base with a resistance layer wherein a thin

resistance layer comprised of an Ni alloy layer containing 2 to 30 wt% of P is formed on the

surface of the conductive base by a method of formation of a thin resistance layer in a plating

bath as set forth in any one of claims 1 to 4 in a range of current density of 1 to 30 A/dm<sup>2</sup>.

Claim 10 (currently amended): A conductive base with a resistance layer wherein a thin

resistance layer comprised of an Ni alloy layer containing 2 to 30 wt% of P is formed on the

surface of the conductive base by a method of formation of a thin resistance layer in a plating

bath as set forth in any one of claims 1 to 4 using an insoluble anode.

Claim 11 (original): A conductive base with a resistance layer as set forth in claim 8

wherein at least the surface on which the resistance layer is formed has a roughness Rz of not

more than 3.5 µm.

Claim 12 (original): A conductive base with a resistance layer as set forth in claim 9

wherein at least the surface on which the resistance layer is formed has a roughness Rz of not

more than 3.5 µm.

Claim 13 (original): A conductive base with a resistance layer as set forth in claim 10

wherein at least the surface on which the resistance layer is formed has a roughness Rz of not

more than 3.5 µm.

Claim 14 (original): A circuit board material with a resistance layer comprised of an

insulating substrate to at least one surface of which a conductive base with a resistance layer as

set forth in claim 8 is adhered with the resistance layer at the base at the inside.

Claim 15 (original): A circuit board material with a resistance layer comprised of an

insulating substrate to at least one surface of which a conductive base with a resistance layer as

set forth in claim 9 is adhered with the resistance layer at the base at the inside.

Claim 16 (original): A circuit board material with a resistance layer comprised of an

insulating substrate to at least one surface of which a conductive base with a resistance layer as

set forth in claim 10 is adhered with the resistance layer at the base at the inside.

Claim 17 (original): A circuit board material with a resistance layer comprised of an

insulating substrate to at least one surface of which a conductive base with a resistance layer as

set forth in claim 11 is adhered with the resistance layer at the base at the inside.

Claim 18 (original): A circuit board material with a resistance layer comprised of an

insulating substrate to at least one surface of which a conductive base with a resistance layer as

set forth in claim 12 is adhered with the resistance layer at the base at the inside.

Claim 19 (original): A circuit board material with a resistance layer comprised of an

insulating substrate to at least one surface of which a conductive base with a resistance layer as

set forth in claim 13 is adhered with the resistance layer at the base at the inside.